

## **RPS50EM** REMOTE PLASMA SOURCE

The RPS50EM is a remote plasma cleaning source, which can be integrated into the SEM or FIB chambers. It efficiently cleans the chamber and sample hydrocarbons through the plasma generated by ionized gas, which can not only alleviate carbon contamination during the imaging process, but also improve the imaging resolution and contrast, and shorten chamber evacuation time. RF-ICP technology makes the plasma softer, which can greatly reduce the thermal damage and plasma bombardment damage during the cleaning process.

Touchscreen automatic control, plug and play.



**Gentle Plasma** 

Low Thermal and Plasma Damage

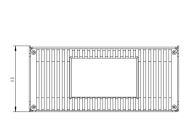
> EM Chamber Gentle Cleaning

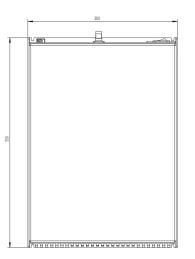
SuPro Instruments LTD

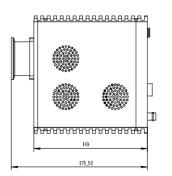
Nanshan, Shenzhen, China www.suproinst.com Tel: 86-755-26642901 Fax: 86-755-26419205 Email: sales@suproinst.com

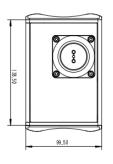


Technical Specifications	Parameters
Working Pressure	0.5-40Pa
RF Power Supply	13.56 MHz RF power supply, RF power adjustable from 10 to 50 W
Gas Module	Standard MFC 100sccm flow meter (N <sub>2</sub> ) / 1 unit
Operation Mode	Touchscreen Control with the Control System Providing Interlock Protection Functions. It Provides Serial Control Commands for Further Development and Programming
Dimension	250mm*350mm*110 mm (Controller) 178.5mm*138.5mm*99.5mm (RF Ion Source)
Weight	~9kg
Connection Method	KF40 Flange Interface
Gas Inlet	Ø6mm Gas Pipe
Power Supply	100-220V AC, 50/60Hz Grounding Triangle Plug
Power Consumption	<200 W
Warranty	One Year
Remark	The technical specifications and parameters listed above will be updated without prior notice. If you have any questions, please contact us









## Controller dimension

Ion Source dimension



Shenzhen SuPro Instruments Co., LtdAddress: B2009, Ruifeng Entrepreneurship Center, Nanshan District, Shenzhen, Guangdong, ChinaTelephone: + 86-755-26642901Fax: + 86-755-26419205E-mail: sales@suproinst.comHttp://www.suproinst.com